ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HIGH-PRESSURE PROCESSING CHAMBER FOR A SEMICONDUCTOR WAFER

Application Number: 10/680783

Confirmation Number: 5859

First Named Applicant: William Jones

Attorney Docket Number:

Art Unit: Examiner:

Search string: (6596093 or 20030196679).pn

<u>Certification:</u> This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:

That no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the certification after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the information disclosure statement.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	6596093	2003-07-22	DeYoung et al.	B2		

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
	1	20030196679	2003-10-23	Cotte et al.	A 1		

Signature

Examiner Name	Date		